L Number	Hits	Search Text	DB	Time stamp
-	100	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:26
-	22	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) same (oxygen O2 "O.sub.2") same (hydrofluorocarbon hydrofluoromethane $3fluoromethane methane adj $3fluoride CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CHF.sub.3 F" "CHF.sub.3")	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/10 16:39
-	8	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) WITH (oxygen O2 "O.sub.2") WITH (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) same (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/17 13:58
-	5	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluoroMETHANE METHYLENE$3FLUORIDE $4FLUOROMETHANE methane adj $3fluoride))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/17 14:00
-	13	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) WITH (oxygen O2 "O.sub.2") WITH (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) same (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluoroMETHANE METHYLENE$3FLUORIDE $4FLUOROMETHANE methane adj $3fluoride)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/01/17 14:00
-	67	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:52
-	55	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 11:53

| | | 22 | (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near2 (inert He Ne Ar Xe helium neon argon xenon)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/03/17 11:57 |
| | | 6 | ((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near2 (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near (inert He Ne Ar Xe helium neon argon xenon)) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/03/17 11:56 |

| - | | 16 | ((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near2 (inert He Ne Ar Xe helium neon argon xenon))) not (((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near2 (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near (inert He Ne Ar Xe helium neon argon xenon))) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2003/03/17 12:02 |

-	33	(((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) not ((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") with (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") with (inert He Ne Ar Xe helium neon argon xenon))) and ((oxygen O2 "O.sub.2") near2 (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") near2 (inert He Ne Ar Xe helium neon argon xenon)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:13
	0	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and etch$3 same (ash$3 (photoresist resist) remov$3 strip$4) same ((single same one) near chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:21
-	0	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((single same one) near chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:21
-	7	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?)) same (Cu copper) and ((oxygen O2 "O.sub.2") same (hydrofluorocarbon fluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3" CF2H2 CF3H CFH3 "CF.sub.2 H.sub.2" "CF.sub.3 H" "CFH.sub.3") same (inert He Ne Ar Xe helium neon argon xenon))) and ((single same one) with chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/17 12:21
-	1408	etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:08

-	6201	etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:11
-	428	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:13
-	115	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:10
-	1234	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:11
-	114	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:12
-	855	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:12
-	80	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:12
-	179	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:16
-	52	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:17
-	38	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:19

-	47	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:19
-	205	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:21

–		323	(((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:21
–		4	((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:21

| - | | 2 | ((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) and (etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen O2 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/03/20 13:31 |

-	2	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen O2 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:31
-	2	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper) with (oxygen O2 "O.sub.2") with (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:32
-	37	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper) same (oxygen O2 "O.sub.2") same (hydrofluorocarbon CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:41
-	2	("6033584").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:45
-	7	6033584.URPN.	USPAT	2004/03/20 13:41
-	5	("5225034" | "5354490" | "5549786" | "5840629" | "5897379").PN.	USPAT	2004/03/20 13:43
-	887	(etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (hydrogen H2 "H.sub.2") with (plasma discharge)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/03/20 13:46

| - | 123 | ((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma discharge) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/03/20 13:46 |

| - | | 75 | (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion))) and (hydrogen H2 "H.sub.2") with (plasma discharge) | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/03/20 13:47 |

| | 79 | (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch\$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 prevent\$3 reduce\$3) with (oxidation oxidiz\$3 corrosion)) (((etch\$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress\$3 inhibit\$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/03/20 13:48 |

| | | 28 | (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3")) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) ((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and etch$3 same ((oxygen O2 "O.sub.2") with (hydrofluorocaron CHF CH2F2 CH3F CHF3 "CH.sub.2 F.sub.2" "CH.sub.3 F" "CHF.sub.3"))) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) same (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 corrosion)) (((etch$3 with (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) and (Cu copper)) and (silicon adj nitride Si3N4 "Si.sub.3 N.sub.4" SiN "SiN.sub.x" Si?sub.? adj N?sub.?) with (Cu copper)) and (oxygen O2 "O.sub.2") with (suppress$3 inhibit$3 prevent$3 reduce$3) with (oxidation oxidiz$3 | USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB | 2004/03/20 13:48 |